

# Wet Bench - Al Etch and Solvent Strip

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## Facts

This bench is set up with two different processes - hot phosphoric acid for aluminum etching and an NMP based stripper for photoresist removal.

- Solvent Strip Tanks use [Baker PRS-2000 Resist Stripper](#)
- Aluminum Etch Tank uses Fuji 16:1:1:2 [Aluminum Etch](#)

## Personnel

- Tool Engineer -
- Process Engineer - [Sean O'Brien](#)
- Process Engineer - [Patricia Meller](#)

## Tool & Process Information

- [Wet Chemical Processing Information](#)

## Manuals & Users

- [Aluminum Etch & Solvent Strip Bench Manual](#)
- [Aluminum Etch & Solvent Strip Wetbench Certification Checklist](#)